

In-situ X-ray studies of heat treatments/nitrogen treatments of Nb

Niobium surface investigations for RF cavity applications.

Guilherme Dalla Lana Semione
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The project

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“Performance improvement of SRF cavities by surface treatment including mechanical polishing and nitrogen thermal treatment”



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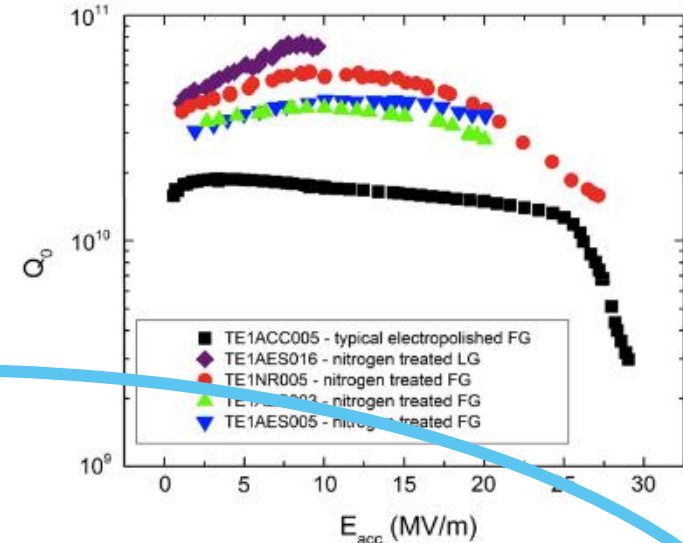
Bundesministerium
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Motivation

Surface preparations of SRF cavities involving N_2

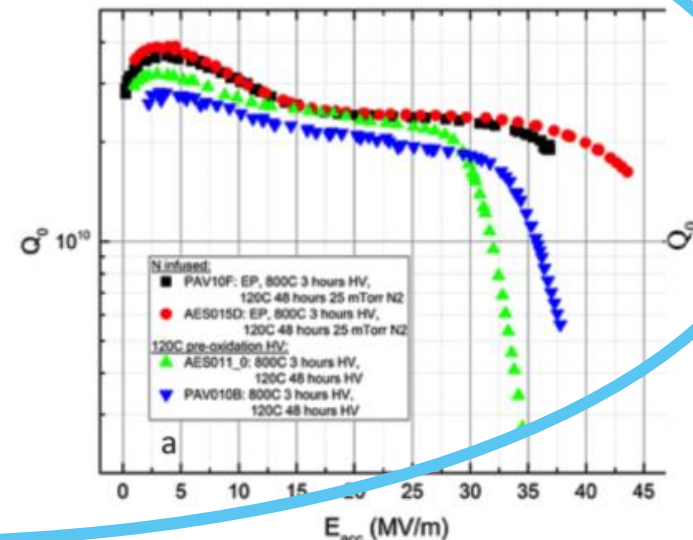
Nitrogen doping:

- 800°C - 1000°C in high vacuum (2-3 hours)
- Addition of $\sim 2.5 \times 10^{-2}$ mbar N_2 (min - hours)
- Material removal: 5-80 μm
- High Q_0 - $E_{\text{acc}} \sim 25$ MV/m



Nitrogen infusion:

- 800°C in high vacuum (2-3 hours)
 - Cooldown to 120°C
 - Addition of $\sim 3 \times 10^{-2}$ mbar N_2 for 48 hours
 - No material removal
- Slightly higher Q_0 - $E_{\text{acc}} > 25$ MV/m



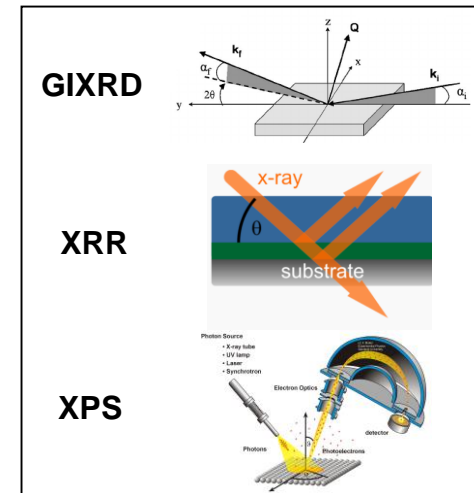
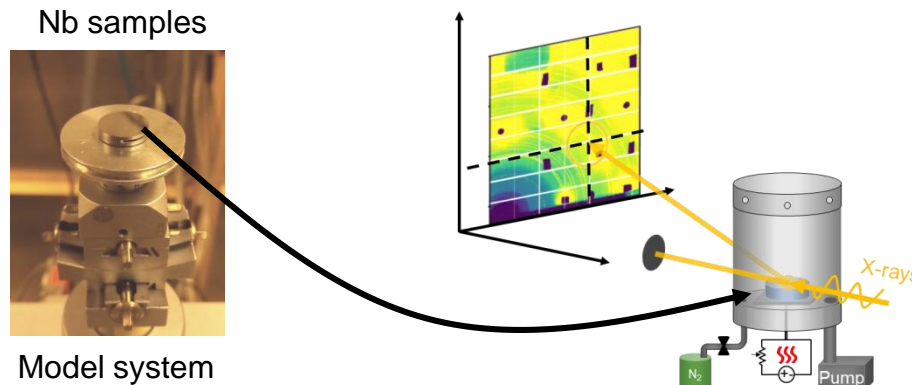
Motivation

Key questions:

- What is the surface state before the treatments?
- How is the surface affected by annealing in high-vacuum?
- Do we promote the formation of different phases (nitrides, oxides) at the surface?
- What happens to possible interstitial atoms (nitrogen, oxygen) during such treatments?
- What happens when the surface is re-exposed to air?

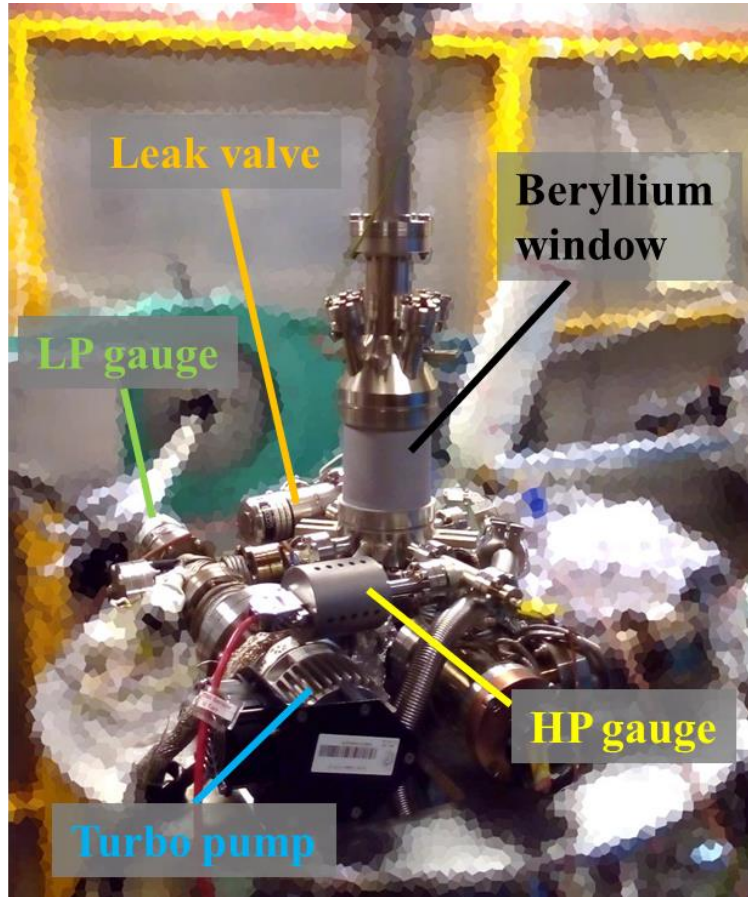
Our approach:

- X-ray based methods to study the near-surface region of Nb before, during and after thermal treatments applied to real Nb SRF cavities



Experimental setup

In-situ X-ray reflectivity and diffraction



- Mobile
- Allows for direct measurements during treatments
- Different gas-conditions
- RT - 1200°C
- Base pressure $\sim 10^{-8}$ mbar
- UHV prep. $\sim 10^{-10}$ mbar



Near-surface region of Nb under annealing

UHV and N₂ atmosphere - Ultraclean sample

ESRF ID31; E = 70 keV



RT



120°C



200°C



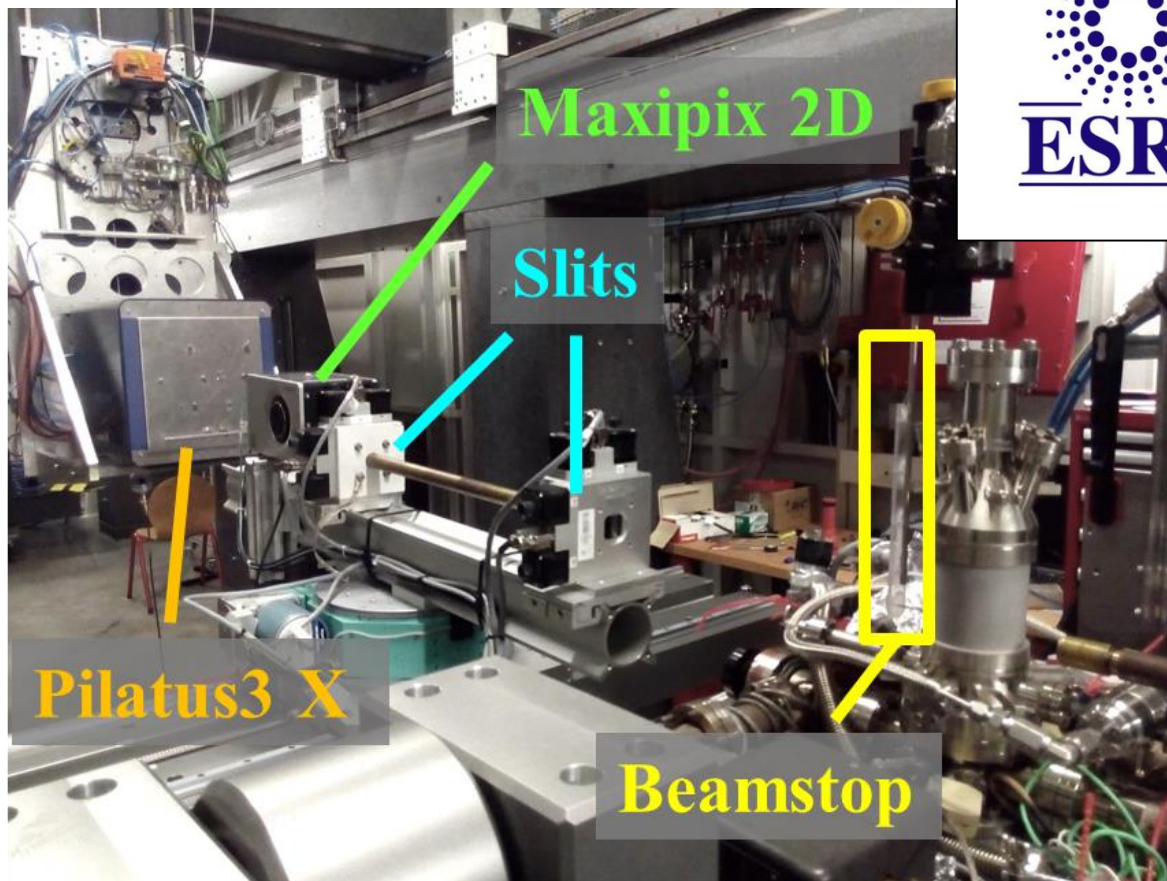
250°C



250°C + N₂



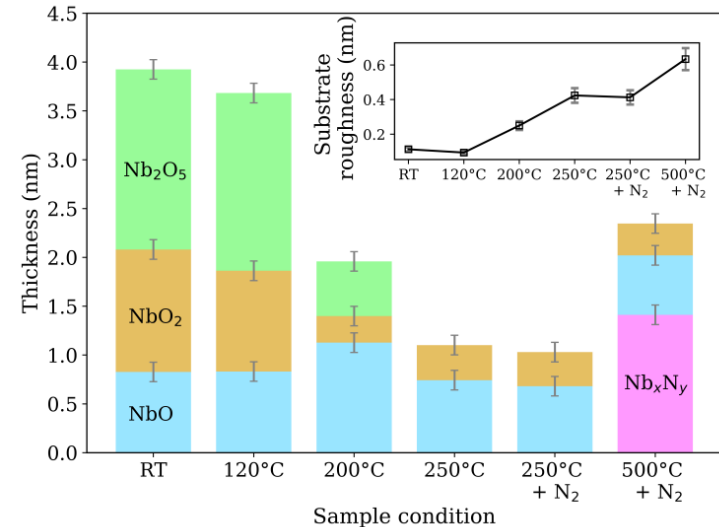
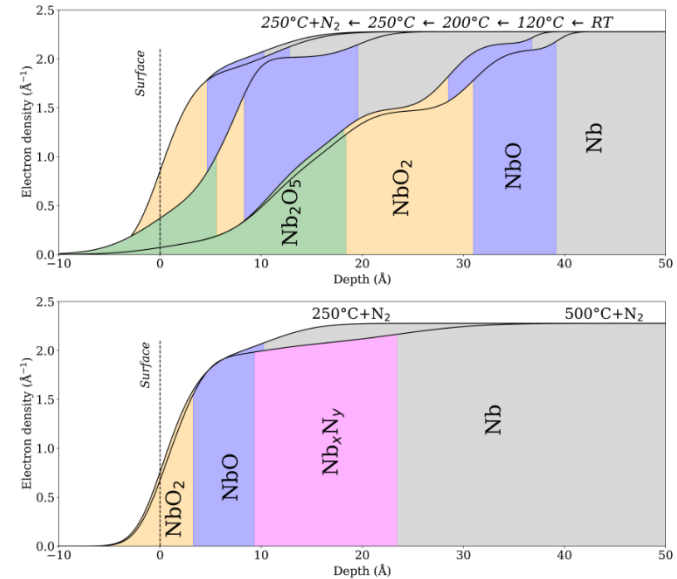
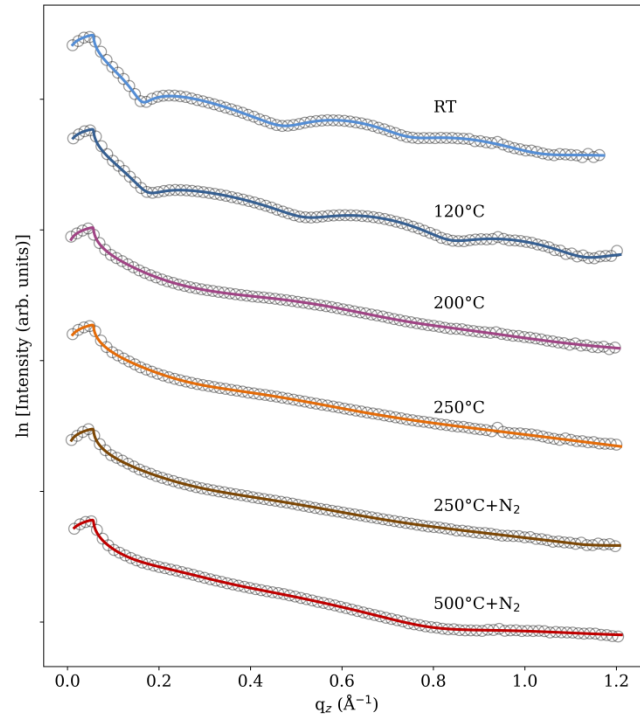
500°C



- Base pressure $\sim 10^{-8}$ mbar
- N₂ pressure = 3.3×10^{-2} mbar (Infusion)
- Each step ~ 10 -12 hours

Near-surface region of Nb under annealing

X-ray Reflectivity: natural oxide consumption

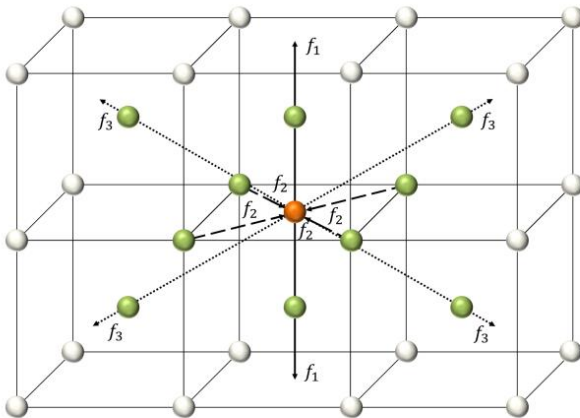


- Initial stage: Nb_2O_5 - NbO_2 - NbO
- Progressive consumption of Nb_2O_5 and NbO_2
- No nitrogen-rich layer detected at $250^\circ\text{C} + \text{N}_2$
- Nb_xN_y layer detected underneath the natural oxides at $500^\circ\text{C} + \text{N}_2$
- Substrate roughness increases with temperature

Near-surface region of Nb under annealing

Interstitial diffuse X-ray scattering

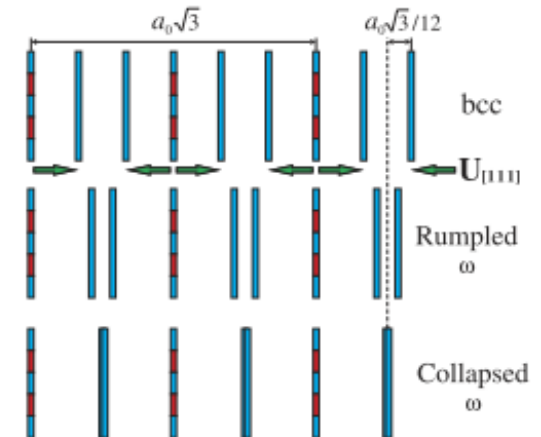
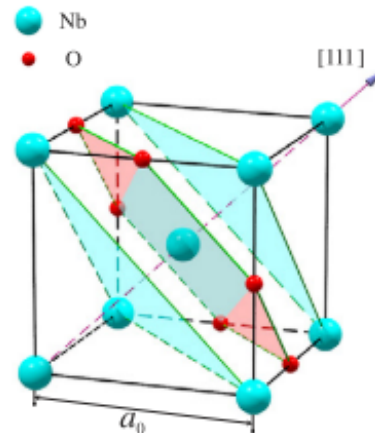
- How to measure the concentration of interstitials in Nb with X-ray diffraction?



- Oxygen/Nitrogen in octahedral site
- Nearest neighbors Nb atoms affected
- bcc Nb \rightarrow soft phonon in $[111]$

Each interstitial is a point-defect:
induces ω phase

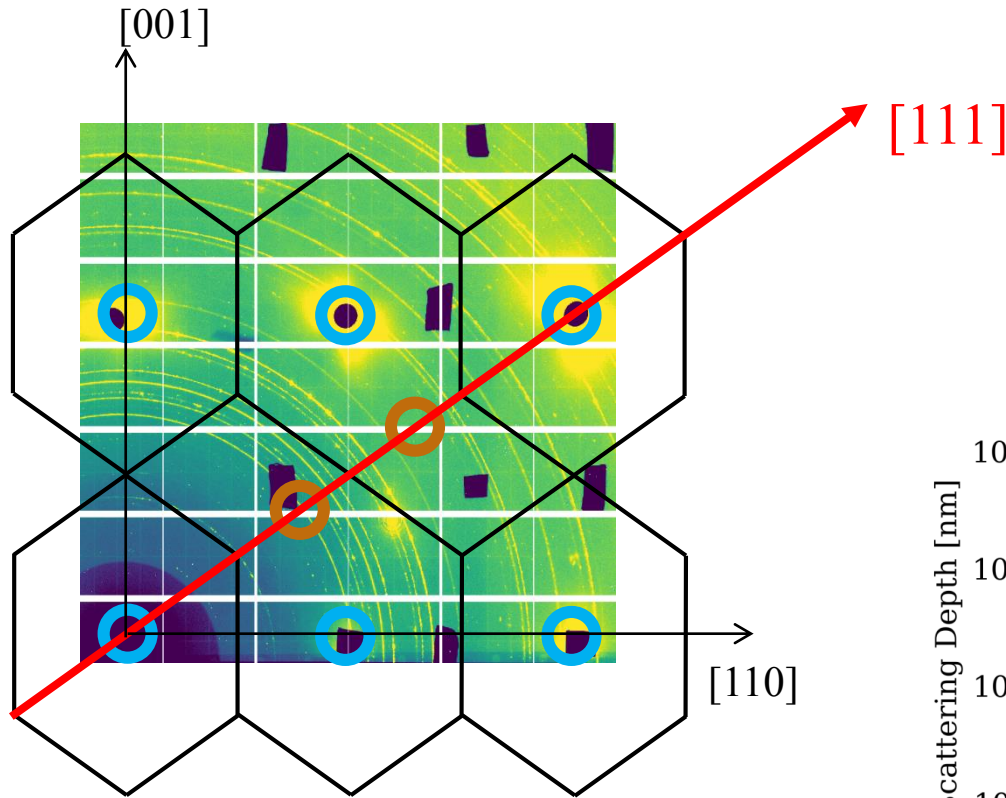
transition bcc \rightarrow hexagonal



R. P. Kurta *et al.* J. Phys. Condens. Matter 20, 275206 (2008)

Near-surface region of Nb under annealing

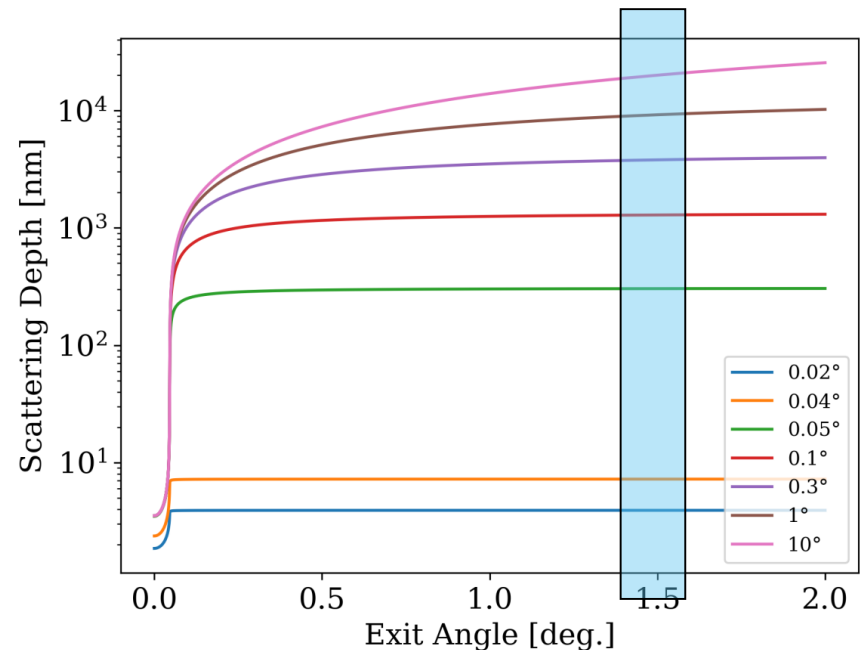
Interstitial diffuse X-ray scattering



$$I \propto c(1 - c)S_D(\mathbf{Q})$$

Depth-resolved:

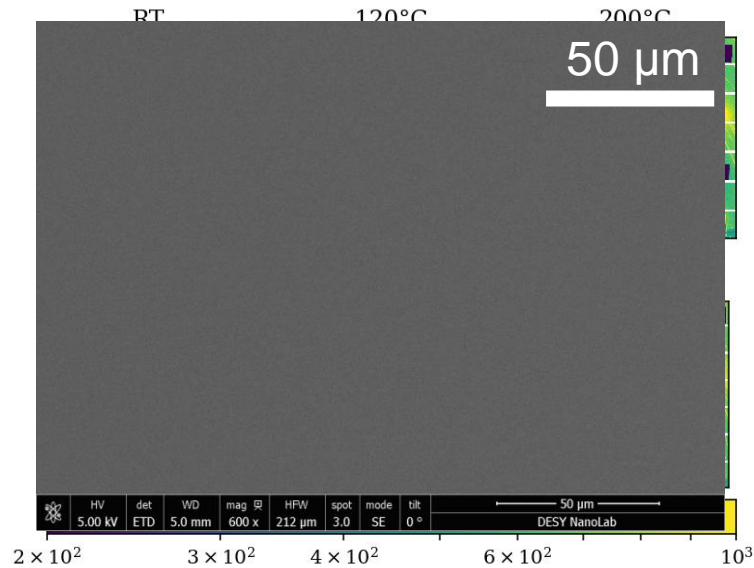
- Tuning incident angle of X-rays



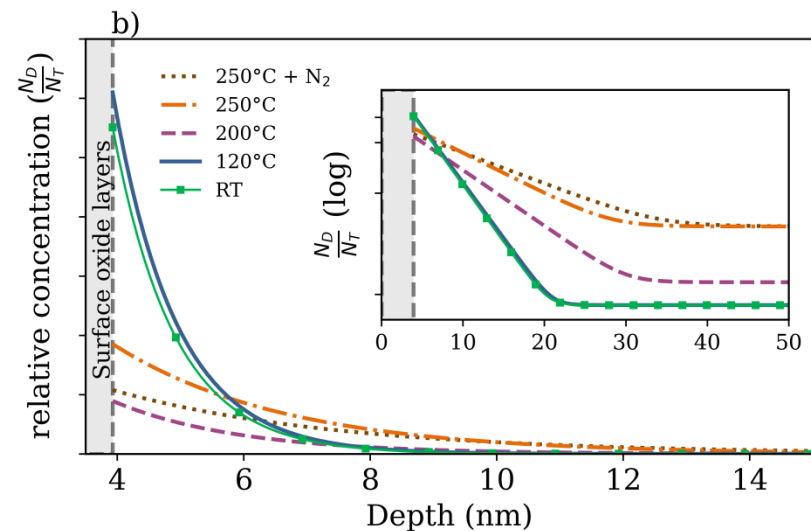
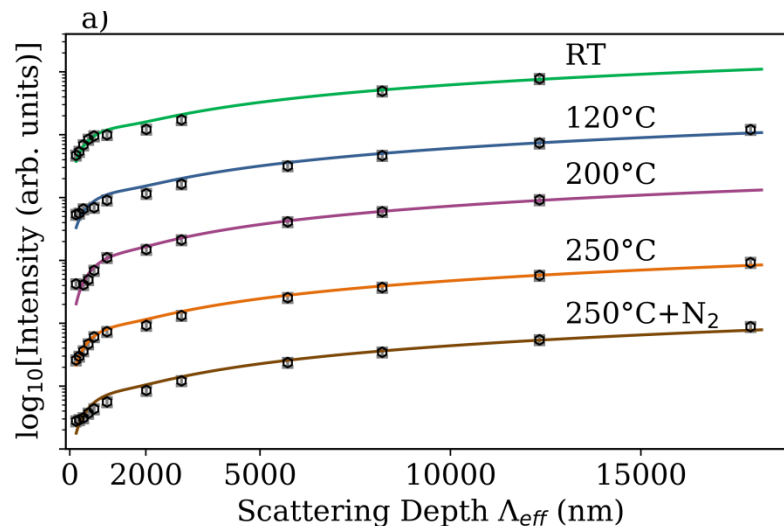
$$c(z) = ae^{(-z-z_0)/\tau} + d, \quad \text{for } z < z_0$$

Near-surface region of Nb under annealing

Interstitial diffuse X-ray scattering

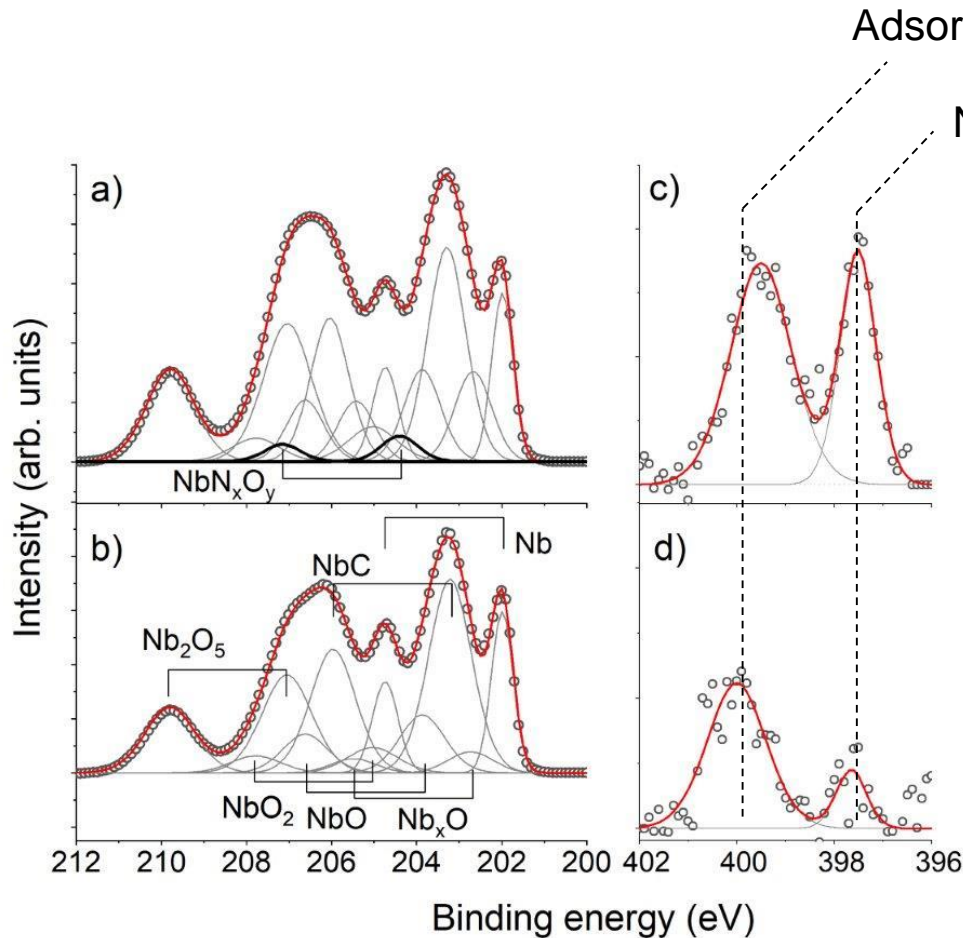


- At 120°C interstitial oxygen is mostly present in the first 10 nm
- Temperature increase leads to further diffusion of oxygen species liberated from the oxide layer
- No evidence of interstitial nitrogen at 250°C



Near-surface region of Nb under annealing

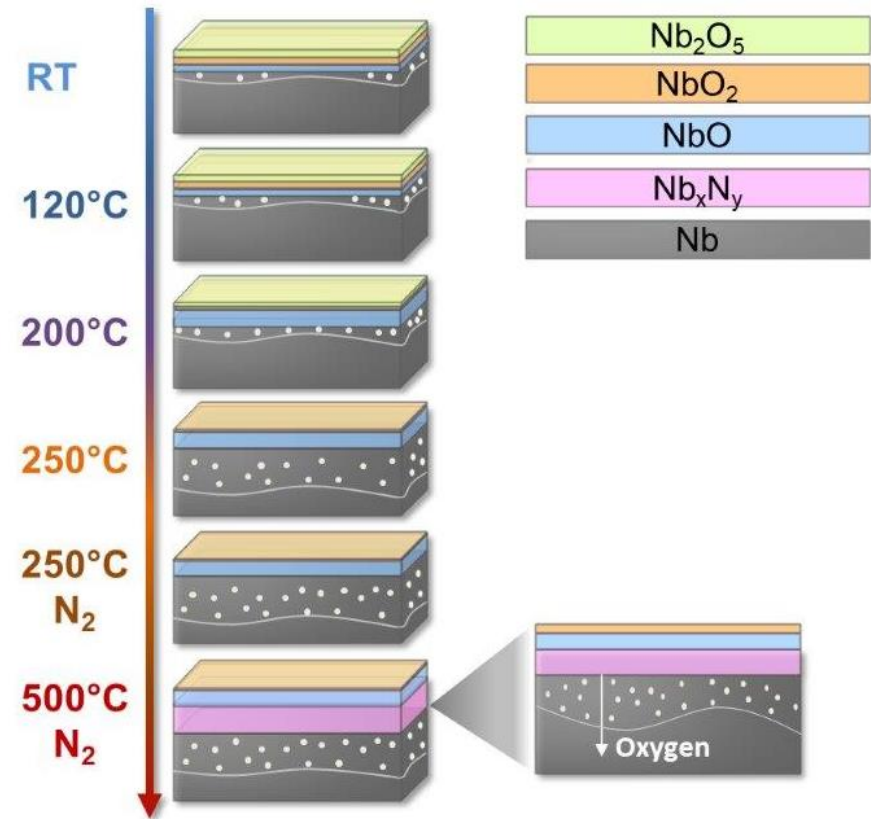
XPS after air exposure



- N 1s: Nb-N and adsorbed N
- Nb 3d: NbN_xO_y with normal exit angle
- Strong NbC presence

Conclusions

- Stepwise annealing in UHV:
 - Progressive consumption of natural oxides
 - Enrichment of the subsurface layer with oxygen interstitials
 - No evidence of N-rich layer or interstitial N at 250°C
 - Nb_xN_y layer formed underneath the oxides at 500°C
 - No precipitates observed



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Thank You.

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